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## Application of SiGe HBT's to Datacom and Wireless

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*(excerpts from the '98 spring MRS meeting)*

## Acknowledgement

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- Our thanks to Dr. Bernard Meyerson and his entire team.

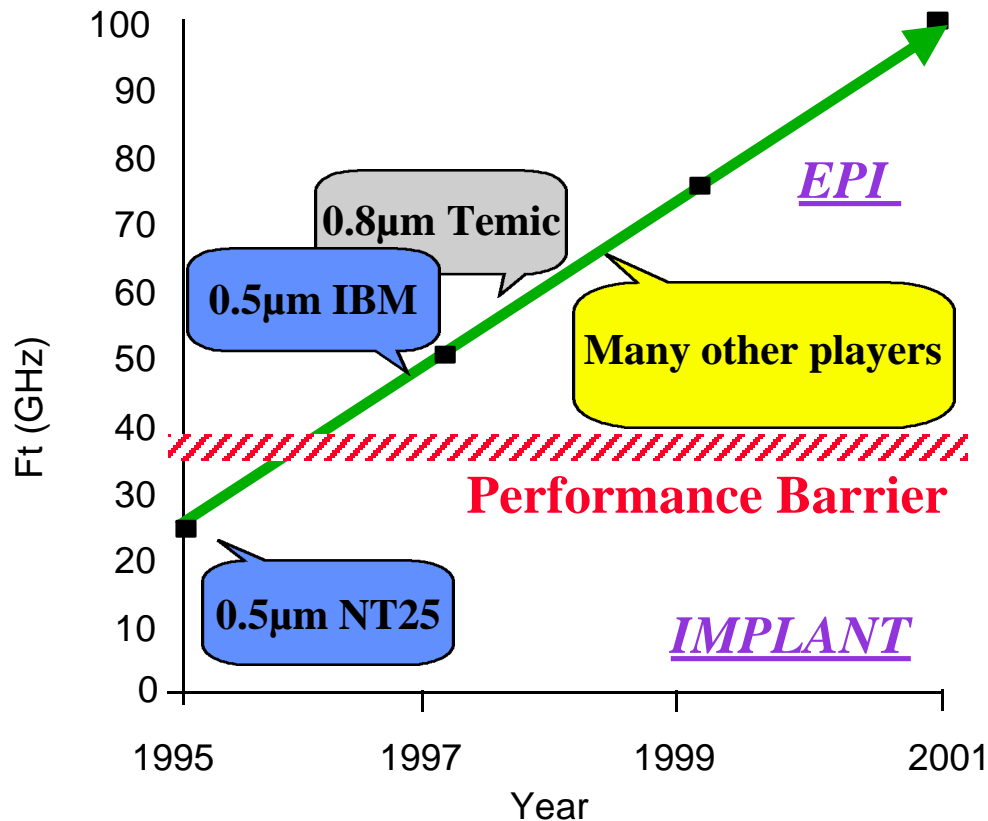
# Agenda

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- Introduction
  - silicon bipolar roadmap
  - technology competition
- SiGe Myths and Truths
  - dispelling some performance myths
  - product directions
- Components
  - available and needs
- Circuits
  - datacom and wireless examples
- Summary

# Introduction

## Silicon Bipolar Roadmap

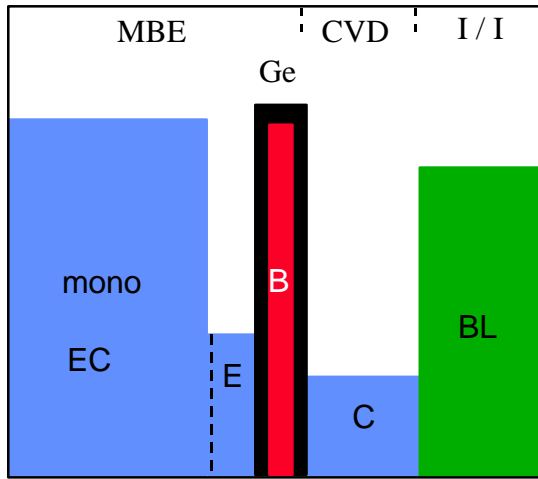


- 25+GHz technology has been available for years
- base layer epi created a significant improvement in performance
- some design rule leveling provided by epi design
- IBM and Temic have pioneered the effort
- many other players have joined the race

*Epi-base transistors are becoming the next stop on the silicon bipolar roadmap!*

# SiGe Myths and Truths

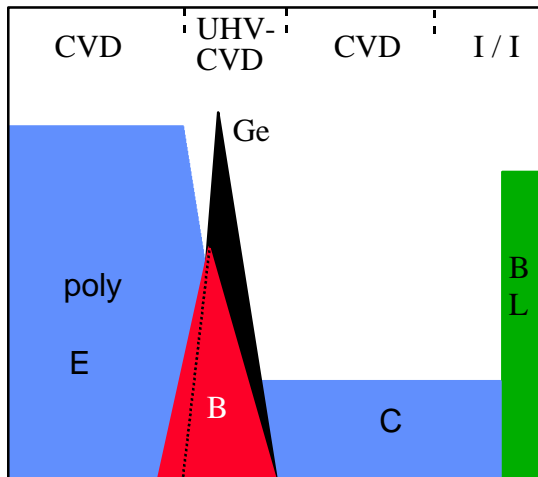
## Not all Transistors are created equal



*> 100GHz  
record Ft!*

### Temic / Daimler Benz (original)

- replicates GaAs HBT's
- 'true' heterostructure
- attempts higher base doping
- lower Rb, NF & higher Fmax
- some design rule levelling (Rb degrade?)
- *discrete to low integration*



*> 100GHz  
record Ft!*

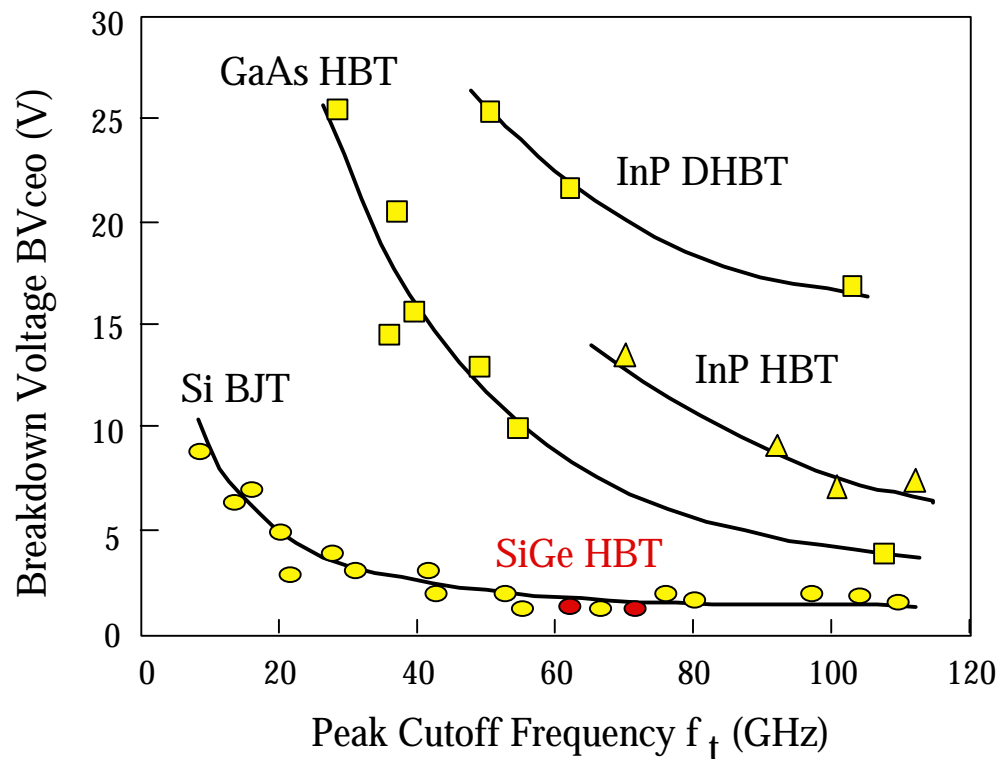
### IBM

- replicates poly emitter homojunction
- 'pseudo' heterostructure
- moderate valence-band offset
- some improvement in base doping
- compatible ULSI CMOS (Rb improve?)
- *moderate to high-level integration*

# SiGe Myths and Truths

## Breakdown voltage is a key operating parameter

Base-Emitter Breakdown Voltage vs Ft



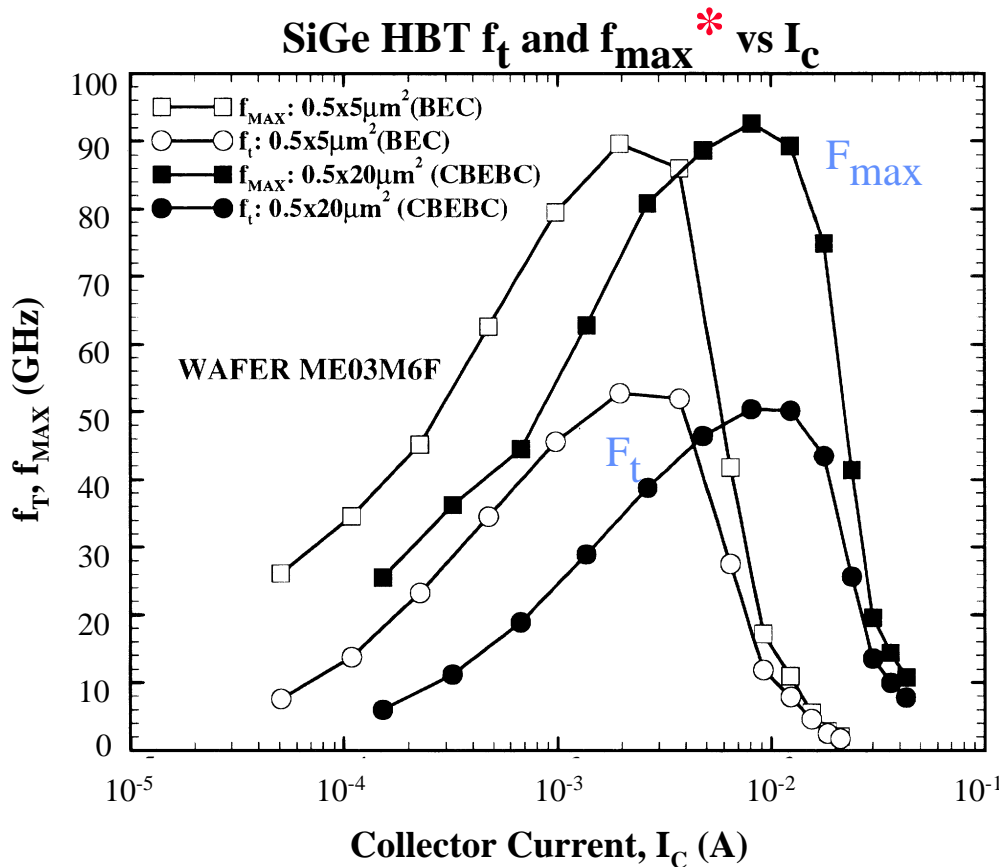
- materials systems define many key characteristics
- $BV_{ce0}$  is considerably lower for silicon
- > 100GHz performance demonstrated @ <2V  $BV_{ce0}$
- low-voltage benefit for low-power dissipation
- > 5V still required for long haul opto components (metro?)
- 3.3 V RF terminals require >6 V  $BV_{ce0}$  for antenna matching (VSWR)

$BV_{CE0}$  vs Peak  $f_t$  courtesy of TRW

***Manufacturers have 50 & 30GHz SiGe devices.***

# Components

## Transistors



\*  $F_{max}$  obtained from  $U(f)$ ; unilateral power gain

### Measured Results

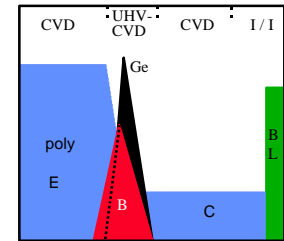
- standard device ( $f_T / f_{max}$  are 50 / 90 GHz)
- no degradation of  $f_T$  and  $f_{max}$  for very small devices
- no degradation of  $f_{max}$  for long devices with proper number of base contacts

### Simulation Accuracy

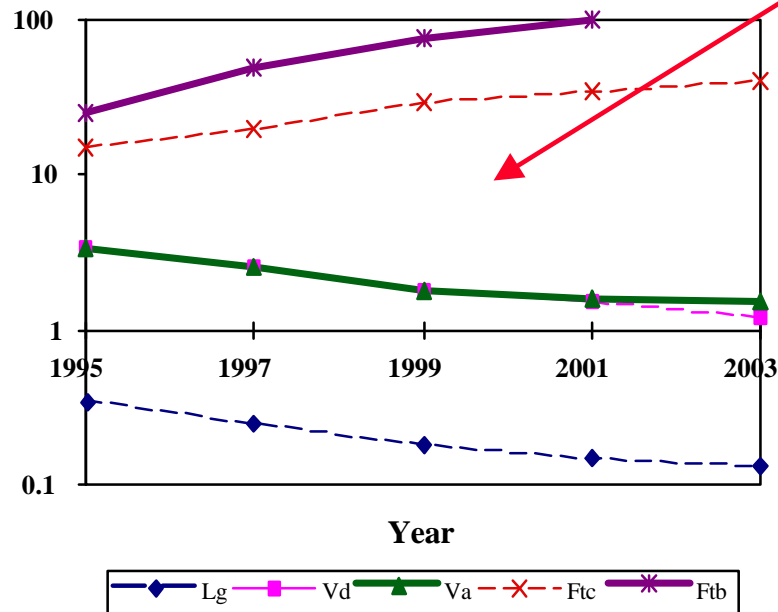
- geometry scalable device characteristics
- per die extracted device characteristics model very accurately
- optimized thermal model parameters included

# SiGe Myths and Truths

*What are the significant advantages offered by SiGe?*



**BiCMOS Parameters vs Time**



- BiCMOS compatible
- follows Si roadmap
  - obeys CMOS scaling (VDD)
  - utilizes silicon investment
- some performance advantage over GaAs
- wafer cost advantage; 8” vs 4”
- systems-on-a-chip integration
  - reduce interfaces, power and packaging costs
- emerging (and existing) market

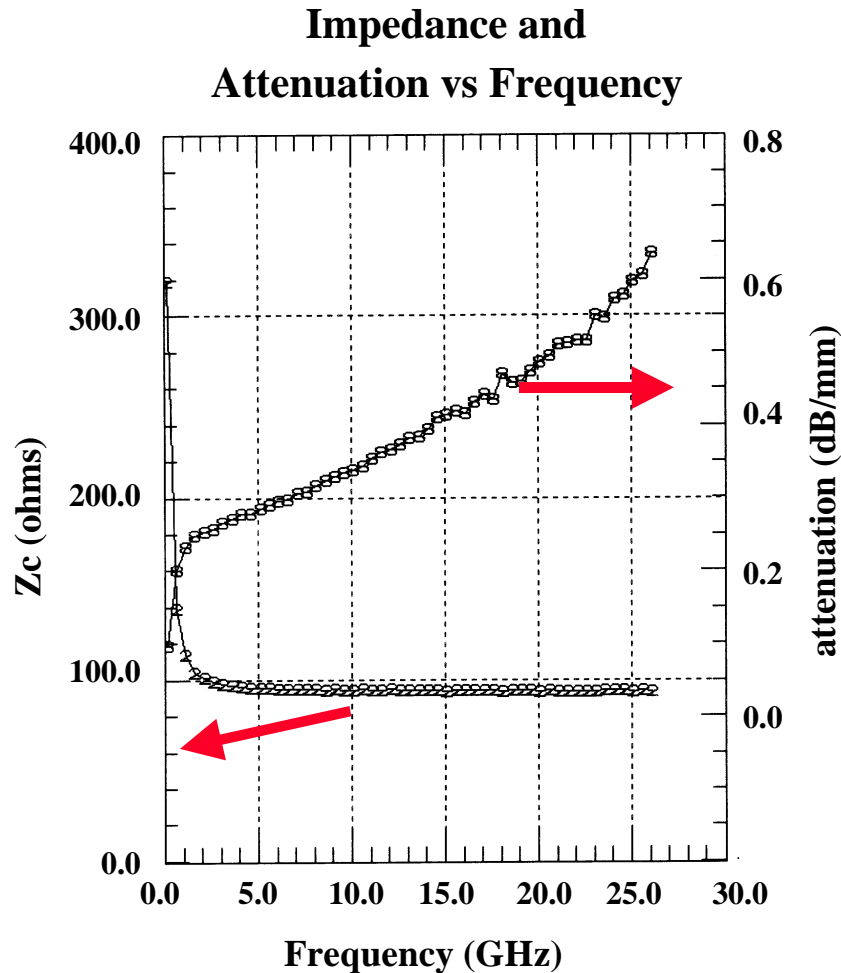
**Capture some GaAs and homojunction market share!**

*discontinuity is good, but predictability helps define product thrusts, CR and customer value*



# Components

## Transmission Lines



### **Measured Results**

- innovative metal over “special” silicon transmission line
- key to circuits from 2 - 20 GHz
- no dispersion; Zc is constant with frequency to 26GHz
- reasonable 0.3 dB/mm loss
- losses better than for metal3 over metal1 lines and/or metal3 over silicon substrate
- no process change required

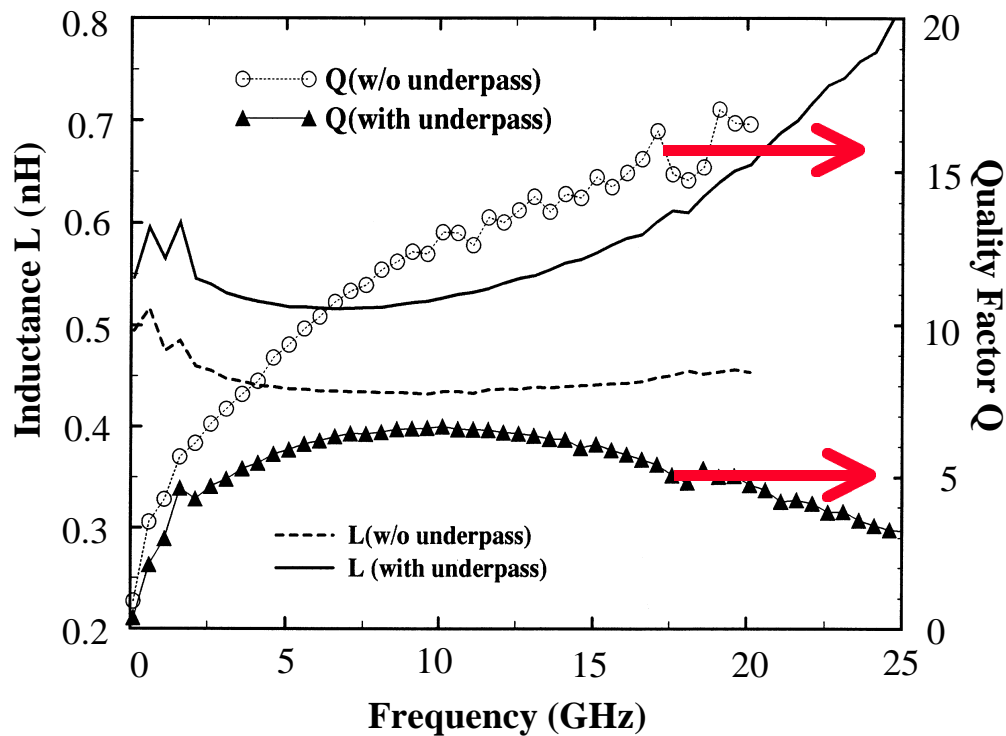
### **Simulation Accuracy**

- better than 10%

# Components

## Spiral Inductors

Inductance Quality Factor vs Freq



2.25 Turns, 30  $\mu\text{m}$  Width, 175 X 175  $\mu\text{m}^2$

### Measured Results

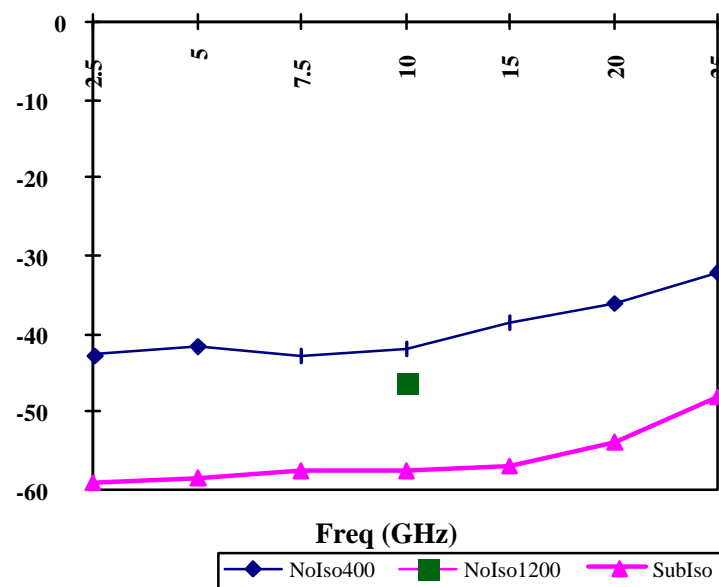
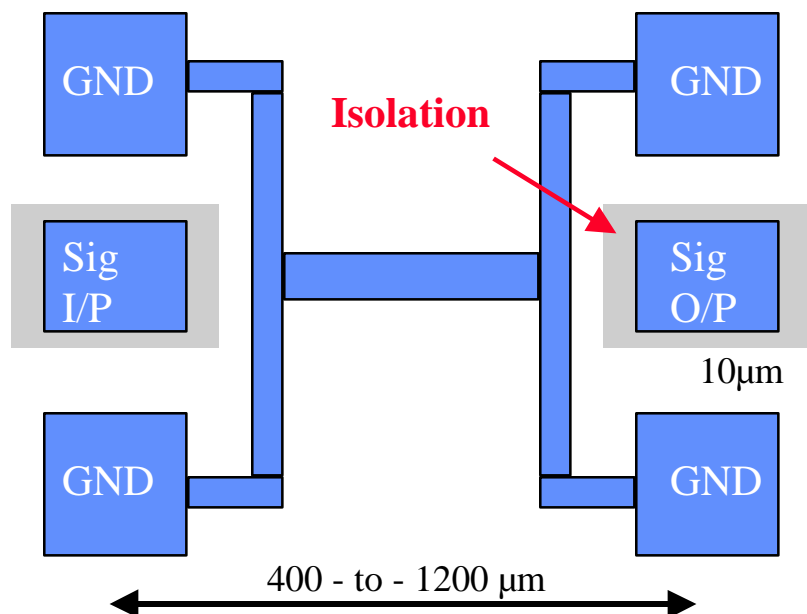
- metal3 spiral inductor (0.45nH @ 10GHz)
- high-current flow (120mA) enabled by metal1 / metal2 underpass
- underpass lowers Quality Factor (12 to 7 @ 10GHz)

### Simulation Accuracy

- special de-embedding structures to determine underpass influence
- better than 5% inductance 20% loss
- more work needed to accurately model losses

# Components

## Substrate Isolation



## Isolations Structures

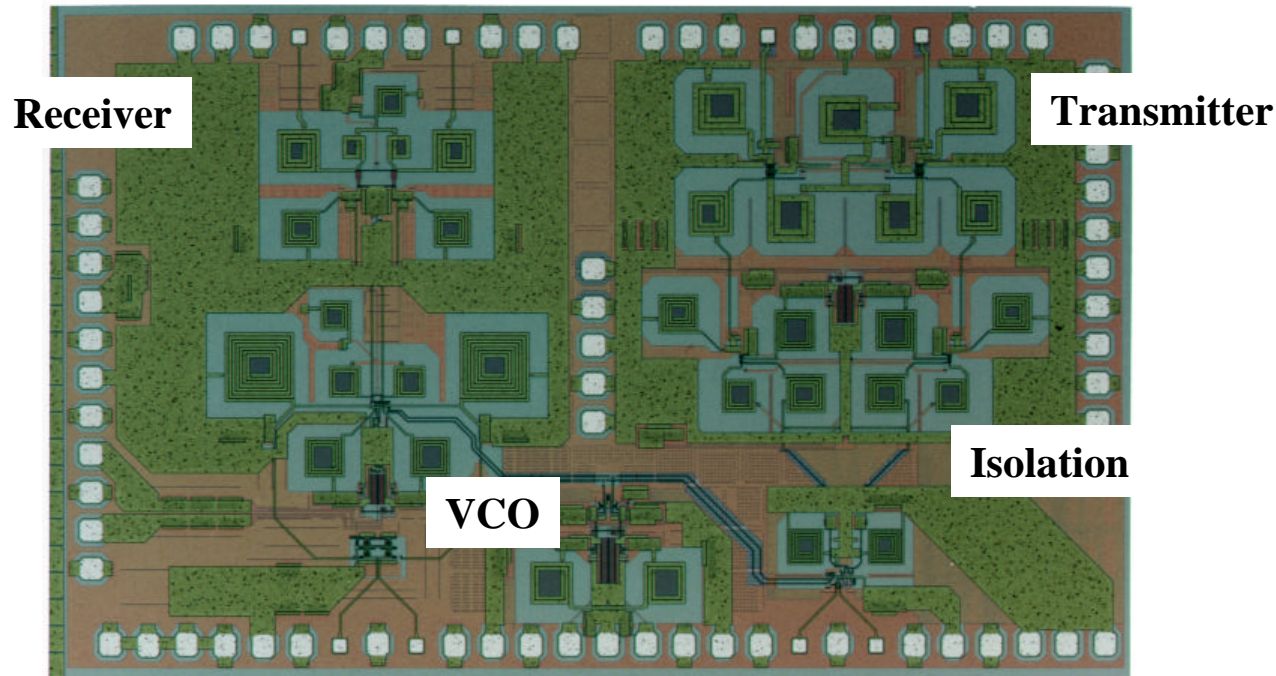
- with and without grounded substrate ring ( p+)
- separation of 400 -to- 1200μm
- full s-parameter characterization

## Results

- Isolation yields -57dB @ 10GHz (no distance dependence down to 400μm)
- better than -50dB to 25GHz (outperforms SOI !!)
- full 15dB improvement over non-isolated case

## 5.2GHz WLAN Radio Transceiver

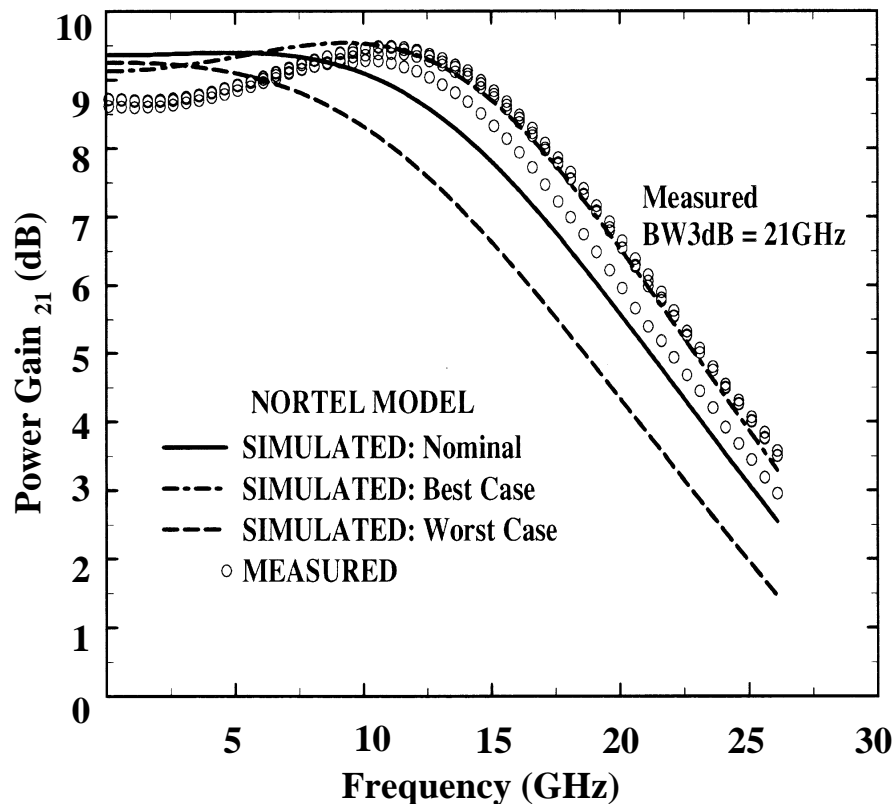
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- Integrated Radio Transceiver using SiGe HBT technology
- Heavily exploits high quality on-chip components (L, varactor, T-line)
- Supports 20MHz bandwidth with on-chip 40dB image rejection
- SSB Noise figure of 5.9dB, IP1=-22dBm and OP1=10dBm
- On-chip VCO with -100dBc/Hz; -128dBc @ 100KHz; 5MHz offsets.
- Draws 125mA in transmit and 45mA in receive mode from 3.5V.

# Circuits

## Broadband Darlington Amplifier - transistors



### Results / Specifications

- Optimized for;
  - broadband BW3dB=21GHz
  - input match  $\approx 20$ dB @  $\approx 5$ GHz
  - P1dB 12.5dBm@5GHz
  - group delay 8 ps across band
  - NF 5.4dB; 1-to-6GHz

### Key Practices

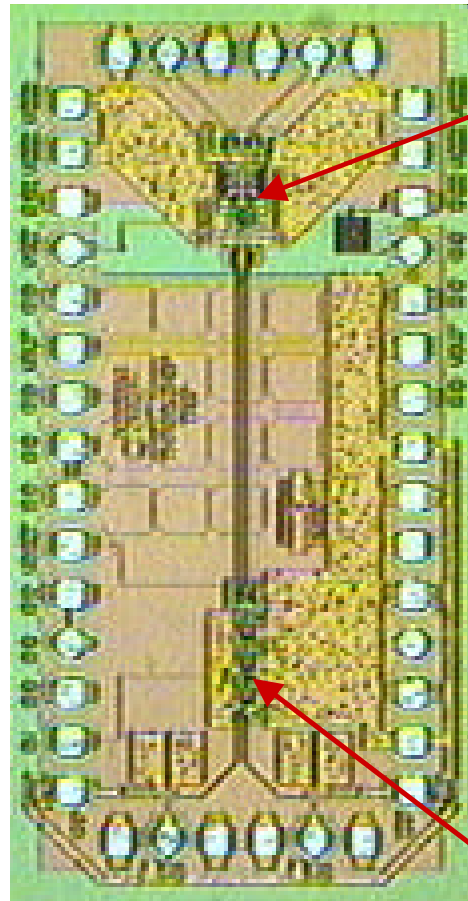
- simultaneous noise & impedance match
- scalable model key to optimize;
  - transistor size
  - optimum bandwidth
  - group delay
- statistical & corner model used
- measured data taken over 3 wafers (lots and lots of die)

# Circuits

## Limiting Amplifier - transmission lines (1st level isolation)

### Results / Specifications

- Small Signal Gain > 60 dB
- Small Signal BW3dB >15 GHz
- Min IP Signal Sensitivity - 3.5 mV  
@ BER of 10<sup>-9</sup> (10<sup>23</sup> PRBS)
- Output Swing (50 ohm) 2.0 V
- Saturation IP V @10Gb/s 1.0 mV
- Voltage supply 5.0 V
- Power Dissipation 0.6 W  
core = 100mW



### Key Practices

#### 50Ω O/P buffer

- 2 volt swing

#### Isolation

- Inductor ground separation

- Transmission line decoupling from input to output

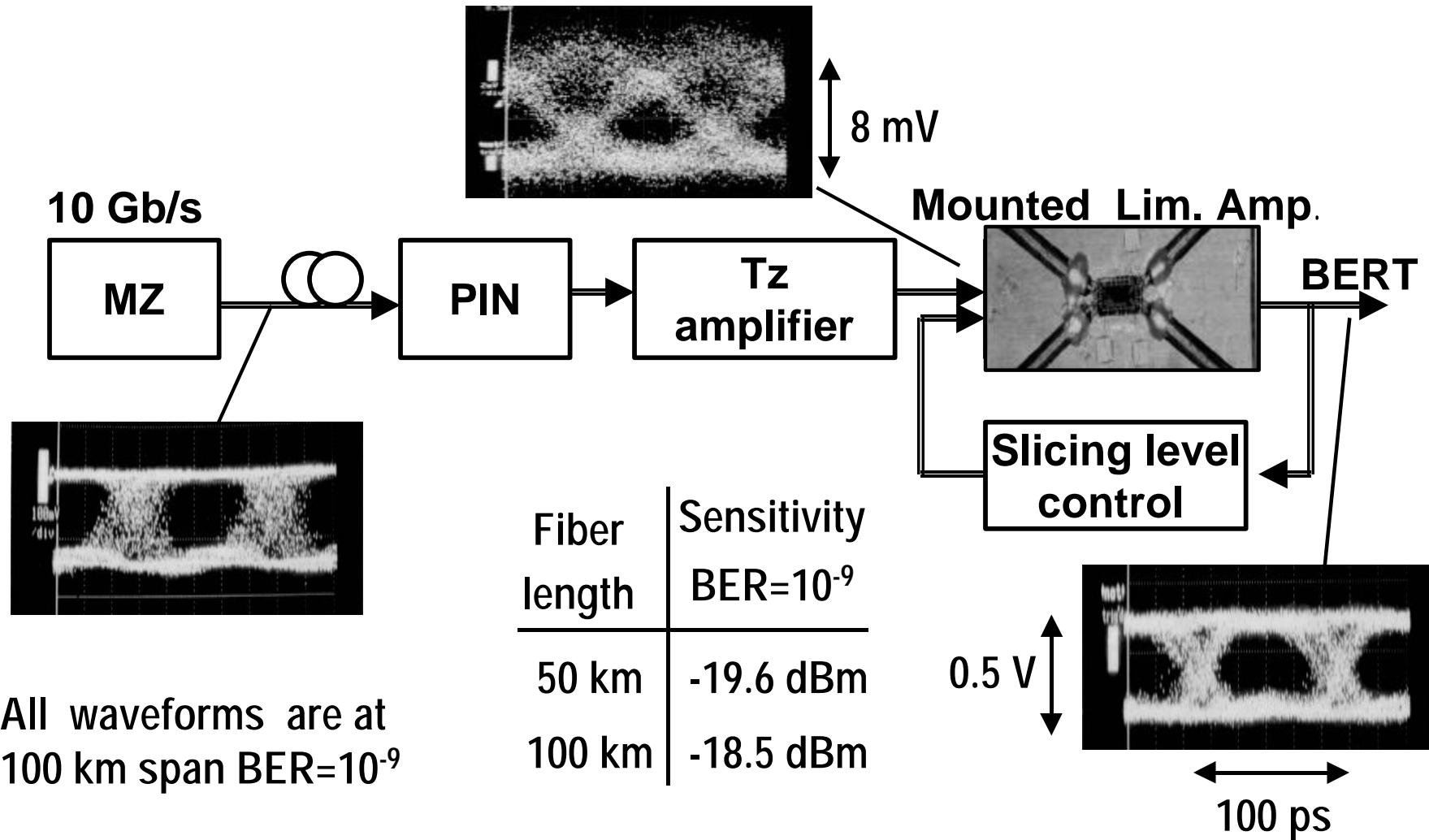
- On-chip capacitive decoupling

#### 50Ω I/P buffer

- 3 gain stages

# Circuits

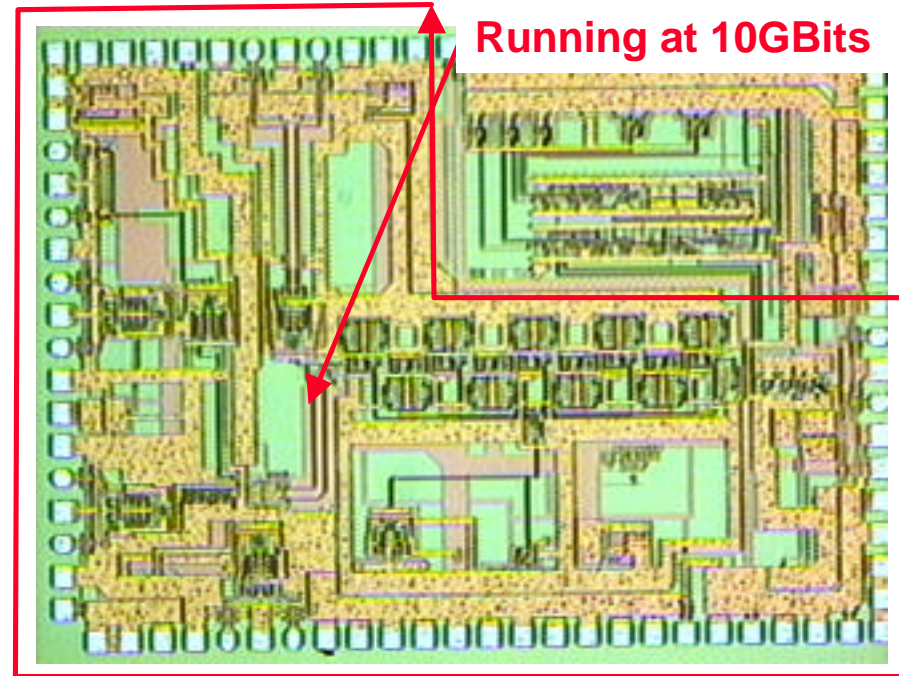
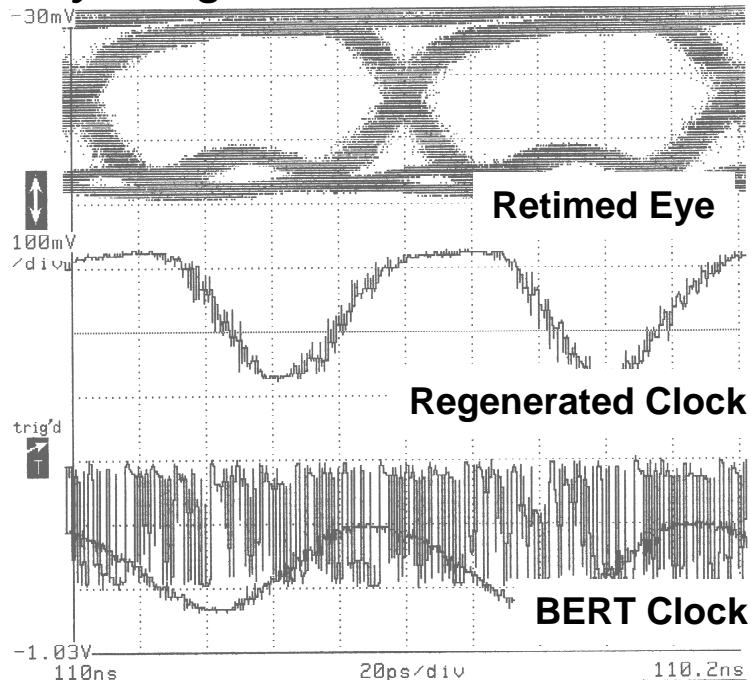
## Optical receiver application



# Circuits

## Highly Integrated Burst Mode Optical Receiver- complexity

### *Eye Diagram*



### *Results / Specifications*

- 1450 transistors; 3mm X 3.5mm
- 30ps Output Rise/Fall Times
- 15mV input sensitivity
- BER <  $10^{-10}$  at  $2^7-1$  pattern at 10 GB/s
- > 200db signal path gain - STABLE

### Key Practices

- fully isolated
- 10 - 20GB/s ECL cell library
- analog decision circuit (limiting amp)
- Full ESD protection



# Circuits

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## SiGe Tests Results Above 10Gb/s

- Limiting amplifier / Decision circuit: 20Gb/s
- 2:1 MUX: 20Gb/s
- 8:1 MUX: 16 Gb/s
- 1:8 Demux: 12.5Gb/s

## Other 10Gb/s Circuits

- Transmit LC VCO
- AGC Amplifier
- Clock and Data Recovery

## Summary

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- **Silicon epi-base technology has extended transistor performance**
  - now encompassed on everyone's roadmap
- **Different heterostructure implementations share constraints**
  - BVceo, lithography, emitter structure
- **Stiff competition for discrete components**
  - silicon has materials and wafer cost advantage
  - packaging / assembly eliminates some of this advantage
- **High-levels of integration provides unique product opportunity**
  - most applicable to > 2.4 - to - 12.5GHz operating frequencies
- **Understanding of passives critical to success**
  - inductors, transmission lines and isolation
- **Imminent very high-performance datacom and wireless systems-on-a-chip solutions**

# SiGe BiCMOS Technology for 10Gb/s Ethernet

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PETER SCHVAN, NORTEL NETWORKS

- SiGe technology can support high speed components for 10Gb/s Receiver and Transmitter Ic's.
  - Tz, Limiting, AGC amplifier
  - Integrated PLL based CDR, 1:n Demux, n:1 MUX
  - Low phase noise VCO (sub-ps jitter)
  - Up to 3V laser/modulator driver
- BiCMOS option allows system-on-chip implementation
  - 0.25 (soon 0.18)um CMOS logic/memory can be integrated
  - High cross-talk suppression demonstrated
- Economics of Si technology guaranties commodity like component cost that follows standard cost reduction curve